

Title (en)
LOW DENSITY POLISHING PAD

Title (de)
POLIERKISSEN MIT NIEDRIGER DICHTHE

Title (fr)
TAMPON DE POLISSAGE À FAIBLE DENSITÉ

Publication
EP 3027363 B1 20200115 (EN)

Application
EP 14747270 A 20140717

Priority
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Abstract (en)
[origin: US2015038066A1] Low density polishing pads and methods of fabricating low density polishing pads are described. In an example, a polishing pad for polishing a substrate includes a polishing body having a density of less than 0.5 g/cc and composed of a thermoset polyurethane material. A plurality of closed cell pores is dispersed in the thermoset polyurethane material.

IPC 8 full level
B24B 37/24 (2012.01)

CPC (source: EP US)
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Citation (examination)
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